

Mikko Ritala

List of Publications by Year in descending order

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543
papers

26,809
citations

8159

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133
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565
all docs

565
docs citations

565
times ranked

17163
citing authors

#	ARTICLE	IF	CITATIONS
1	Crystallinity of inorganic films grown by atomic layer deposition: Overview and general trends. Journal of Applied Physics, 2013, 113, .	1.1	1,190
2	Atomic layer deposition (ALD): from precursors to thin film structures. Thin Solid Films, 2002, 409, 138-146.	0.8	1,092
3	Atomic Layer Deposition Chemistry: Recent Developments and Future Challenges. Angewandte Chemie - International Edition, 2003, 42, 5548-5554.	7.2	934
4	Atomic Layer Deposition of Oxide Thin Films with Metal Alkoxides as Oxygen Sources. Science, 2000, 288, 319-321.	6.0	452
5	Atomic Layer Deposition of Platinum Thin Films. Chemistry of Materials, 2003, 15, 1924-1928.	3.2	360
6	Atomic Layer Deposition of Noble Metals and Their Oxides. Chemistry of Materials, 2014, 26, 786-801.	3.2	308
7	Atomic layer deposition. , 2002, , 103-159.		293
8	Growth of titanium dioxide thin films by atomic layer epitaxy. Thin Solid Films, 1993, 225, 288-295.	0.8	292
9	X-ray ptychographic computed tomography at 16â€¦nm isotropic 3D resolution. Scientific Reports, 2014, 4, 3857.	1.6	281
10	Titanium isopropoxide as a precursor in atomic layer epitaxy of titanium dioxide thin films. Chemistry of Materials, 1993, 5, 1174-1181.	3.2	271
11	Perfectly Conformal TiN and Al ₂ O ₃ Films Deposited by Atomic Layer Deposition. Chemical Vapor Deposition, 1999, 5, 7-9.	1.4	271
12	Atomic layer epitaxy - a valuable tool for nanotechnology?. Nanotechnology, 1999, 10, 19-24.	1.3	270
13	Thin Film Deposition Methods for CuInSe ₂ Solar Cells. Critical Reviews in Solid State and Materials Sciences, 2005, 30, 1-31.	6.8	270
14	Ruthenium Thin Films Grown by Atomic Layer Deposition. Chemical Vapor Deposition, 2003, 9, 45-49.	1.4	249
15	Photoswitchable Superabsorbency Based on Nanocellulose Aerogels. Advanced Functional Materials, 2011, 21, 510-517.	7.8	240
16	Effect of water dose on the atomic layer deposition rate of oxide thin films. Thin Solid Films, 2000, 368, 1-7.	0.8	239
17	Tailoring the dielectric properties of HfO ₂ â€¦Ta ₂ O ₅ nanolaminates. Applied Physics Letters, 1996, 68, 3737-3739.	1.5	215
18	Reaction Mechanism Studies on Atomic Layer Deposition of Ruthenium and Platinum. Electrochemical and Solid-State Letters, 2003, 6, C130.	2.2	207

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19	Atomic Layer Deposition of Photocatalytic TiO ₂ Thin Films from Titanium Tetramethoxide and Water. Chemical Vapor Deposition, 2004, 10, 143-148.	1.4	204
20	Low-temperature atomic layer deposition of Al ₂ O ₃ thin coatings for corrosion protection of steel: Surface and electrochemical analysis. Corrosion Science, 2011, 53, 2168-2175.	3.0	199
21	Development of crystallinity and morphology in hafnium dioxide thin films grown by atomic layer epitaxy. Thin Solid Films, 1994, 250, 72-80.	0.8	197
22	Atomic Layer Deposition of Hafnium Dioxide Films from Hafnium Tetrakis(ethylmethanamide) and Water. Chemical Vapor Deposition, 2002, 8, 199-204.	1.4	192
23	Titanium isopropoxide as a precursor for atomic layer deposition: characterization of titanium dioxide growth process. Applied Surface Science, 2000, 161, 385-395.	3.1	187
24	Atomic Layer Deposition in Nanometer-Level Replication of Cellulosic Substances and Preparation of Photocatalytic TiO ₂ /Cellulose Composites. Journal of the American Chemical Society, 2005, 127, 14178-14179.	6.6	180
25	Controlled Growth of TaN, Ta ₃ N ₅ , and TaO _x N _y Thin Films by Atomic Layer Deposition. Chemistry of Materials, 1999, 11, 1712-1718.	3.2	157
26	Zirconium dioxide thin films deposited by ALE using zirconium tetrachloride as precursor. Applied Surface Science, 1994, 75, 333-340.	3.1	156
27	Zone-Doubling Technique to Produce Ultrahigh-Resolution X-Ray Optics. Physical Review Letters, 2007, 99, 264801.	2.9	154
28	Atomic layer deposition of noble metals: Exploration of the low limit of the deposition temperature. Journal of Materials Research, 2004, 19, 3353-3358.	1.2	152
29	Crystallization in hafnia- and zirconia-based systems. Physica Status Solidi (B): Basic Research, 2004, 241, 2268-2278.	0.7	149
30	Growth of SrTiO ₃ and BaTiO ₃ Thin Films by Atomic Layer Deposition. Electrochemical and Solid-State Letters, 1999, 2, 504.	2.2	148
31	Atomic Layer Deposition of Metal Tellurides and Selenides Using Alkylsilyl Compounds of Tellurium and Selenium. Journal of the American Chemical Society, 2009, 131, 3478-3480.	6.6	147
32	In Situ Quartz Crystal Microbalance and Quadrupole Mass Spectrometry Studies of Atomic Layer Deposition of Aluminum Oxide from Trimethylaluminum and Water. Langmuir, 2001, 17, 6506-6509.	1.6	146
33	Atomic Layer Epitaxy Growth of TiN Thin Films. Journal of the Electrochemical Society, 1995, 142, 2731-2737.	1.3	137
34	Atomic Layer Deposition of Ruthenium Thin Films from Ru(thd) ₃ and Oxygen. Chemical Vapor Deposition, 2004, 10, 215-219.	1.4	137
35	Rare-earth oxide thin films for gate dielectrics in microelectronics. Journal of Alloys and Compounds, 2006, 418, 27-34.	2.8	136
36	Atomic Layer Deposition of Iridium Thin Films. Journal of the Electrochemical Society, 2004, 151, G489.	1.3	135

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37	Growth of In ₂ S ₃ thin films by atomic layer epitaxy. Applied Surface Science, 1994, 82-83, 122-125.	3.1	130
38	Synthesis of oxide thin films and overlayers by atomic layer epitaxy for advanced applications. Materials Science and Engineering B: Solid-State Materials for Advanced Technology, 1996, 41, 23-29.	1.7	130
39	Comparison of hafnium oxide films grown by atomic layer deposition from iodide and chloride precursors. Thin Solid Films, 2002, 416, 72-79.	0.8	128
40	Hollow Inorganic Nanospheres and Nanotubes with Tunable Wall Thicknesses by Atomic Layer Deposition on Self-Assembled Polymeric Templates. Advanced Materials, 2007, 19, 102-106.	11.1	126
41	Nanofocusing of hard X-ray free electron laser pulses using diamond based Fresnel zone plates. Scientific Reports, 2011, 1, 57.	1.6	126
42	Influence of sol and surface properties on in vitro bioactivity of sol-gel-derived TiO ₂ and TiO ₂ -SiO ₂ films deposited by dip-coating method. , 1998, 42, 295-302.		124
43	Atomic Layer Epitaxy Growth of Tantalum Oxide Thin Films from Ta ₂ O ₅ and H ₂ O. Electrochemical Society, 1995, 142, 1670-1675.	1.3	122
44	Reaction Mechanism Studies on Titanium Isopropoxide-Water Atomic Layer Deposition Process. Chemical Vapor Deposition, 2002, 8, 21.	1.4	119
45	Properties of Ta ₂ O ₅ -Based Dielectric Nanolaminates Deposited by Atomic Layer Epitaxy. Journal of the Electrochemical Society, 1997, 144, 300-306.	1.3	118
46	Atomic layer deposition of TiO ₂ -xNx thin films for photocatalytic applications. Journal of Photochemistry and Photobiology A: Chemistry, 2006, 177, 68-75.	2.0	117
47	Atomic Layer Deposition of High-k Oxides of the Group 4 Metals for Memory Applications. Advanced Engineering Materials, 2009, 11, 223-234.	1.6	116
48	Atomic Layer Deposition of Nanostructured TiO ₂ Photocatalysts via Template Approach. Chemistry of Materials, 2007, 19, 1816-1820.	3.2	115
49	Ultra-high resolution zone-doubled π -diffractive X-ray optics for the multi-keV regime. Optics Express, 2011, 19, 175.	1.7	114
50	In Situ Mass Spectrometry Study on Surface Reactions in Atomic Layer Deposition of Al ₂ O ₃ Thin Films from Trimethylaluminum and Water. Langmuir, 2000, 16, 4034-4039.	1.6	111
51	Advanced thin film technology for ultrahigh resolution X-ray microscopy. Ultramicroscopy, 2009, 109, 1360-1364.	0.8	111
52	Industrial Applications of Atomic Layer Deposition. ECS Transactions, 2009, 25, 641-652.	0.3	110
53	Rare-earth oxide thin films as gate oxides in MOSFET transistors. Journal of Solid State Chemistry, 2003, 171, 170-174.	1.4	108
54	Plasma-Enhanced Atomic Layer Deposition of Silver Thin Films. Chemistry of Materials, 2011, 23, 2901-2907.	3.2	106

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55	Atomic Layer Deposition of SrTiO ₃ Thin Films from a Novel Strontium Precursor-Strontium-bis(tri-isopropyl cyclopentadienyl). <i>Chemical Vapor Deposition</i> , 2001, 7, 75-80.	1.4	105
56	Electrodeposition of Cu on Ru Barrier Layers for Damascene Processing. <i>Journal of the Electrochemical Society</i> , 2006, 153, C37.	1.3	104
57	Use of 1,1-Dimethylhydrazine in the Atomic Layer Deposition of Transition Metal Nitride Thin Films. <i>Journal of the Electrochemical Society</i> , 2000, 147, 3377.	1.3	103
58	Atomic layer epitaxy growth of titanium dioxide thin films from titanium ethoxide. <i>Chemistry of Materials</i> , 1994, 6, 556-561.	3.2	100
59	Influence of growth temperature on properties of zirconium dioxide films grown by atomic layer deposition. <i>Journal of Applied Physics</i> , 2002, 92, 1833-1840.	1.1	100
60	Development of Dielectric Properties of Niobium Oxide, Tantalum Oxide, and Aluminum Oxide Based Nanolayered Materials. <i>Journal of the Electrochemical Society</i> , 2001, 148, F35.	1.3	99
61	In Situ Quadrupole Mass Spectrometry and Quartz Crystal Microbalance Studies on the Atomic Layer Deposition of Titanium Dioxide from Titanium Tetrachloride and Water. <i>Chemistry of Materials</i> , 2001, 13, 4506-4511.	3.2	98
62	Atomic Layer Deposition of Crystalline MoS ₂ Thin Films: New Molybdenum Precursor for Low-Temperature Film Growth. <i>Advanced Materials Interfaces</i> , 2017, 4, 1700123.	1.9	98
63	Selective-Area Atomic Layer Deposition Using Poly(methyl methacrylate) Films as Mask Layers. <i>Journal of Physical Chemistry C</i> , 2008, 112, 15791-15795.	1.5	96
64	Thermal study on electrospun polyvinylpyrrolidone/ammonium metatungstate nanofibers: optimising the annealing conditions for obtaining WO ₃ nanofibers. <i>Journal of Thermal Analysis and Calorimetry</i> , 2011, 105, 73-81.	2.0	95
65	Low-Temperature Deposition of Zirconium Oxide-Based Nanocrystalline Films by Alternate Supply of Zr[OC(CH ₃) ₃] ₄ and H ₂ O. <i>Chemical Vapor Deposition</i> , 2000, 6, 297-302.	1.4	94
66	Atomic layer epitaxy growth of aluminum oxide thin films from a novel Al(CH ₃) ₂ Cl precursor and H ₂ O. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1997, 15, 2214-2218.	0.9	93
67	Atomic Layer Deposition of Platinum Oxide and Metallic Platinum Thin Films from Pt(acac) ₂ and Ozone. <i>Chemistry of Materials</i> , 2008, 20, 6840-6846.	3.2	90
68	<i>In Situ</i> Studies on Reaction Mechanisms in Atomic Layer Deposition. <i>Critical Reviews in Solid State and Materials Sciences</i> , 2013, 38, 167-202.	6.8	90
69	Surface modification of thermoplastics by atomic layer deposition of Al ₂ O ₃ and TiO ₂ thin films. <i>European Polymer Journal</i> , 2008, 44, 3564-3570.	2.6	88
70	Tantalum oxide nanocoatings prepared by atomic layer and filtered cathodic arc deposition for corrosion protection of steel: Comparative surface and electrochemical analysis. <i>Electrochimica Acta</i> , 2013, 90, 232-245.	2.6	88
71	AFM studies on ZnS thin films grown by atomic layer epitaxy. <i>Applied Surface Science</i> , 1997, 120, 43-50.	3.1	86
72	Advanced ALE processes of amorphous and polycrystalline films. <i>Applied Surface Science</i> , 1997, 112, 223-230.	3.1	84

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73	History of atomic layer deposition and its relationship with the American Vacuum Society. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2013, 31, .	0.9	84
74	Lithium Phosphate Thin Films Grown by Atomic Layer Deposition. Journal of the Electrochemical Society, 2012, 159, A259-A263.	1.3	83
75	Surface Chemistry, Reactivity, and Pore Structure of Porous Silicon Oxidized by Various Methods. Langmuir, 2012, 28, 10573-10583.	1.6	82
76	Introducing atomic layer epitaxy for the deposition of optical thin films. Thin Solid Films, 1996, 289, 250-255.	0.8	81
77	Novel ALD Process for Depositing CaF ₂ Thin Films. Chemistry of Materials, 2007, 19, 3387-3392.	3.2	81
78	Atomic force microscopy study of titanium dioxide thin films grown by atomic layer epitaxy. Thin Solid Films, 1993, 228, 32-35.	0.8	80
79	Some recent developments in the MOCVD and ALD of high- ϵ^{p} dielectric oxides. Journal of Materials Chemistry, 2004, 14, 3101-3112.	6.7	78
80	Atomic layer deposition of zirconium oxide from zirconium tetraiodide, water and hydrogen peroxide. Journal of Crystal Growth, 2001, 231, 262-272.	0.7	77
81	Atomic layer deposition and characterization of vanadium oxide thin films. RSC Advances, 2013, 3, 1179-1185.	1.7	77
82	Atomic layer deposition of hafnium dioxide thin films from hafnium tetrakis(dimethylamide) and water. Thin Solid Films, 2005, 491, 328-338.	0.8	76
83	Studies on atomic layer deposition of MOF-5 thin films. Microporous and Mesoporous Materials, 2013, 182, 147-154.	2.2	76
84	Atomic layer deposition of TiO ₂ thin films from TiI ₄ and H ₂ O. Applied Surface Science, 2002, 193, 277-286.	3.1	75
85	The preparation of reusable magnetic and photocatalytic composite nanofibers by electrospinning and atomic layer deposition. Nanotechnology, 2009, 20, 035602.	1.3	75
86	Precursors as enablers of ALD technology: Contributions from University of Helsinki. Coordination Chemistry Reviews, 2013, 257, 3297-3322.	9.5	75
87	Bismuth precursors for atomic layer deposition of bismuth-containing oxide films. Journal of Materials Chemistry, 2004, 14, 3191-3197.	6.7	74
88	Ruthenium/aerogel nanocomposites via atomic layer deposition. Nanotechnology, 2007, 18, 055303.	1.3	74
89	Atomic Layer Deposition of Emerging 2D Semiconductors, HfS ₂ and ZrS ₂ , for Optoelectronics. Chemistry of Materials, 2019, 31, 5713-5724.	3.2	72
90	In situ study of atomic layer epitaxy growth of tantalum oxide thin films from Ta(OC ₂ H ₅) ₅ and H ₂ O. Applied Surface Science, 1997, 112, 236-242.	3.1	71

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91	Characterization of titanium dioxide atomic layer growth from titanium ethoxide and water. <i>Thin Solid Films</i> , 2000, 370, 163-172.	0.8	71
92	Atomic layer deposited thin films for corrosion protection. <i>European Physical Journal Special Topics</i> , 1999, 09, Pr8-493-Pr8-499.	0.2	70
93	Structural and dielectric properties of thin ZrO ₂ films on silicon grown by atomic layer deposition from cyclopentadienyl precursor. <i>Journal of Applied Physics</i> , 2004, 95, 84-91.	1.1	70
94	Novel mixed alkylamido-cyclopentadienyl precursors for ALD of ZrO ₂ thin films. <i>Journal of Materials Chemistry</i> , 2008, 18, 5243.	6.7	70
95	Study of a novel ALD process for depositing MgF ₂ thin films. <i>Journal of Materials Chemistry</i> , 2007, 17, 5077.	6.7	69
96	Corrosion protection of aluminium by ultra-thin atomic layer deposited alumina coatings. <i>Corrosion Science</i> , 2016, 106, 16-24.	3.0	68
97	Low temperature deposition of AlN films by an alternate supply of trimethyl aluminum and ammonia. <i>Chemical Vapor Deposition</i> , 1996, 2, 277-283.	1.4	67
98	Exploitation of atomic layer deposition for nanostructured materials. <i>Materials Science and Engineering C</i> , 2007, 27, 1504-1508.	3.8	67
99	Molecular Organization of the Tear Fluid Lipid Layer. <i>Biophysical Journal</i> , 2010, 99, 2559-2567.	0.2	67
100	Electrochemical and time-of-flight secondary ion mass spectrometry analysis of ultra-thin metal oxide (Al ₂ O ₃ and Ta ₂ O ₅) coatings deposited by atomic layer deposition on stainless steel. <i>Electrochimica Acta</i> , 2011, 56, 10516-10523.	2.6	67
101	Electrodeposition of PbTe thin films. <i>Thin Solid Films</i> , 1998, 326, 78-82.	0.8	66
102	Low-Temperature Deposition of Aluminum Oxide by Radical Enhanced Atomic Layer Deposition. <i>Journal of the Electrochemical Society</i> , 2005, 152, F90.	1.3	66
103	Growth and phase stabilization of HfO ₂ thin films by ALD using novel precursors. <i>Journal of Crystal Growth</i> , 2010, 312, 245-249.	0.7	66
104	Atomic Layer Epitaxy Growth of TiN Thin Films from TiI ₄ and NH ₃ . <i>Journal of the Electrochemical Society</i> , 1998, 145, 2914-2920.	1.3	65
105	Radical-Enhanced Atomic Layer Deposition of Silver Thin Films Using Phosphine-Adducted Silver Carboxylates. <i>Chemical Vapor Deposition</i> , 2007, 13, 408-413.	1.4	65
106	Failure mechanism of thin Al ₂ O ₃ coatings grown by atomic layer deposition for corrosion protection of carbon steel. <i>Electrochimica Acta</i> , 2011, 56, 9609-9618.	2.6	65
107	Effect of selected atomic layer deposition parameters on the structure and dielectric properties of hafnium oxide films. <i>Journal of Applied Physics</i> , 2004, 96, 5298-5307.	1.1	64
108	Controlled growth of HfO ₂ thin films by atomic layer deposition from cyclopentadienyl-type precursor and water. <i>Journal of Materials Chemistry</i> , 2005, 15, 2271.	6.7	64

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109	Atomic layer deposition of Ge ₂ Sb ₂ Te ₅ thin films. <i>Microelectronic Engineering</i> , 2009, 86, 1946-1949.	1.1	64
110	Selective-Area Atomic Layer Deposition Using Poly(vinyl pyrrolidone) as a Passivation Layer. <i>Journal of the Electrochemical Society</i> , 2010, 157, K10.	1.3	64
111	Properties of hafnium oxide films grown by atomic layer deposition from hafnium tetraiodide and oxygen. <i>Journal of Applied Physics</i> , 2002, 92, 5698-5703.	1.1	63
112	Growth of In ₂ O ₃ Thin Films by Atomic Layer Epitaxy. <i>Journal of the Electrochemical Society</i> , 1994, 141, 3210-3213.	1.3	62
113	Deposition of copper films by an alternate supply of CuCl and Zn. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1997, 15, 2330-2333.	0.9	62
114	Photocatalytic Properties of WO ₃ /TiO ₂ Core/Shell Nanofibers prepared by Electrospinning and Atomic Layer Deposition. <i>Chemical Vapor Deposition</i> , 2013, 19, 149-155.	1.4	62
115	Analysis of AlN thin films by combining TOF-ERDA and NRB techniques. <i>Thin Solid Films</i> , 1996, 289, 159-165.	0.8	61
116	Electrodeposition of lead selenide thin films. <i>Journal of Materials Chemistry</i> , 1998, 8, 651-654.	6.7	61
117	Selective-area atomic layer deposition with microcontact printed self-assembled octadecyltrichlorosilane monolayers as mask layers. <i>Thin Solid Films</i> , 2008, 517, 972-975.	0.8	61
118	Effect of thickness of ALD grown TiO ₂ films on photoelectrocatalysis. <i>Journal of Photochemistry and Photobiology A: Chemistry</i> , 2009, 204, 200-208.	2.0	61
119	Sealing of Hard CrN and DLC Coatings with Atomic Layer Deposition. <i>ACS Applied Materials & Interfaces</i> , 2014, 6, 1893-1901.	4.0	61
120	Electrochemical preparation of In and Al doped ZnO thin films for CuInSe ₂ solar cells. <i>Thin Solid Films</i> , 2003, 434, 20-23.	0.8	60
121	Properties of HfO ₂ Thin Films Grown by ALD from Hafnium tetrakis(ethylmethanamide) and Water. <i>Journal of the Electrochemical Society</i> , 2004, 151, F189.	1.3	60
122	H ₂ S modified atomic layer deposition process for photocatalytic TiO ₂ thin films. <i>Journal of Materials Chemistry</i> , 2007, 17, 1361-1371.	6.7	60
123	Atomic Layer Deposition of Iridium Oxide Thin Films from Ir(acac) ₃ and Ozone. <i>Chemistry of Materials</i> , 2008, 20, 2903-2907.	3.2	60
124	Radical-Enhanced Atomic Layer Deposition of Metallic Copper Thin Films. <i>Journal of the Electrochemical Society</i> , 2005, 152, G25.	1.3	59
125	Self-Assembled Octadecyltrimethoxysilane Monolayers Enabling Selective-Area Atomic Layer Deposition of Iridium. <i>Chemical Vapor Deposition</i> , 2006, 12, 415-417.	1.4	59
126	One-Step Electrodeposition of Cu _{2-x} Se and CuInSe ₂ Thin Films by the Induced Co-deposition Mechanism. <i>Journal of the Electrochemical Society</i> , 2000, 147, 1080.	1.3	58

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127	Corrosion Protection of Steel with Oxide Nanolaminates Grown by Atomic Layer Deposition. <i>Journal of the Electrochemical Society</i> , 2011, 158, C369.	1.3	58
128	Atomic Layer Deposition of Rhenium Disulfide. <i>Advanced Materials</i> , 2018, 30, e1703622.	11.1	58
129	Atomic Layer Deposition and Chemical Vapor Deposition of Tantalum Oxide by Successive and Simultaneous Pulsing of Tantalum Ethoxide and Tantalum Chloride. <i>Chemistry of Materials</i> , 2000, 12, 1914-1920.	3.2	57
130	Atomic Layer Deposition of Hafnium Dioxide Films from 1-Methoxy-2-methyl-2-propanolate Complex of Hafnium. <i>Chemistry of Materials</i> , 2003, 15, 1722-1727.	3.2	57
131	Atomic Layer Deposition of Molybdenum Nitride Thin Films for Cu Metallizations. <i>Journal of the Electrochemical Society</i> , 2005, 152, G361.	1.3	57
132	Needleless electrospinning with twisted wire spinneret. <i>Nanotechnology</i> , 2015, 26, 025301.	1.3	57
133	Properties of atomic layer deposited (Ta _{1-x} Nb _x) ₂ O ₅ solid solution films and Ta ₂ O ₅ /Nb ₂ O ₅ nanolaminates. <i>Journal of Applied Physics</i> , 1999, 86, 5656-5662.	1.1	56
134	Recent developments in the MOCVD and ALD of rare earth oxides and silicates. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2005, 118, 97-104.	1.7	56
135	Atomic Layer Deposition and Properties of Lanthanum Oxide and Lanthanum-Aluminum Oxide Films. <i>Chemical Vapor Deposition</i> , 2006, 12, 158-164.	1.4	55
136	Conformality of remote plasma-enhanced atomic layer deposition processes: An experimental study. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012, 30, .	0.9	55
137	In Situ Mass Spectrometry Study on Atomic Layer Deposition from Metal (Ti, Ta, and Nb) Ethoxides and Water. <i>Chemistry of Materials</i> , 2001, 13, 817-823.	3.2	54
138	ALD of Rhodium Thin Films from Rh(acac) ₃ and Oxygen. <i>Electrochemical and Solid-State Letters</i> , 2005, 8, C99.	2.2	54
139	Osteogenic and osteoclastogenic differentiation of co-cultured cells in polylactic acid/nanohydroxyapatite fiber scaffolds. <i>Journal of Biotechnology</i> , 2015, 204, 53-62.	1.9	54
140	Studies on the morphology of Al ₂ O ₃ thin films grown by atomic layer epitaxy. <i>Thin Solid Films</i> , 1996, 286, 54-58.	0.8	53
141	Electrochemical quartz crystal microbalance study of the electrodeposition mechanisms of Cu _{2-x} Se thin films. <i>Electrochimica Acta</i> , 2000, 45, 3737-3748.	2.6	53
142	Influence of atomic layer deposition parameters on the phase content of Ta ₂ O ₅ films. <i>Journal of Crystal Growth</i> , 2000, 212, 459-468.	0.7	53
143	Reaction mechanism studies on the zirconium chloride/water atomic layer deposition process. <i>Journal of Materials Chemistry</i> , 2002, 12, 1484-1489.	6.7	53
144	Atomic Layer Deposition of BaTiO ₃ Thin Films—Effect of Barium Hydroxide Formation. <i>Chemical Vapor Deposition</i> , 2007, 13, 239-246.	1.4	53

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145	Niobium Oxide Thin Films Grown by Atomic Layer Epitaxy. <i>Chemical Vapor Deposition</i> , 1998, 04, 29-34.	1.4	53
146	Atomic Layer Deposition of Ta(Al)N(C) Thin Films Using Trimethylaluminum as a Reducing Agent. <i>Journal of the Electrochemical Society</i> , 2001, 148, G566.	1.3	52
147	Evaluation of a Praseodymium Precursor for Atomic Layer Deposition of Oxide Dielectric Films. <i>Chemistry of Materials</i> , 2004, 16, 5162-5168.	3.2	52
148	Atomic Layer Deposition of Ruthenium Films from (Ethylcyclopentadienyl)(pyrrolyl)ruthenium and Oxygen. <i>Journal of the Electrochemical Society</i> , 2011, 158, D158.	1.3	52
149	Atomic Layer CVD in the Biâ€“Tiâ€“O System. <i>Chemical Vapor Deposition</i> , 2000, 6, 139-145.	1.4	51
150	Atomic Layer Deposition of Titanium Oxide from TiI ₄ and H ₂ O ₂ . <i>Chemical Vapor Deposition</i> , 2000, 6, 303-310.	1.4	51
151	Synthesis and characterisation of cyclopentadienyl complexes of barium: precursors for atomic layer deposition of BaTiO ₃ . <i>Dalton Transactions</i> , 2004, , 1181-1188.	1.6	51
152	The Atomic Layer Deposition of HfO ₂ and ZrO ₂ using Advanced Metallocene Precursors and H ₂ O as the Oxygen Source. <i>Chemical Vapor Deposition</i> , 2008, 14, 358-365.	1.4	51
153	In Situ Reaction Mechanism Studies on Atomic Layer Deposition of ZrO ₂ from (CpMe) ₂ Zr(OMe)Me and Water or Ozone. <i>Chemistry of Materials</i> , 2008, 20, 5698-5705.	3.2	51
154	Atomic Layer Deposition of Iridium Thin Films by Consecutive Oxidation and Reduction Steps. <i>Chemistry of Materials</i> , 2009, 21, 4868-4872.	3.2	51
155	Large-area plasmonic hot-spot arrays: sub-2 nm interparticle separations with plasma-enhanced atomic layer deposition of Ag on periodic arrays of Si nanopillars. <i>Optics Express</i> , 2011, 19, 26056.	1.7	51
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